

Form 1449*

Atty. Docket No.: 303.603US1

Serial No. 09/382,929

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

Applicant: Paul A. Farrar

Filing Date: August 25, 1999

Group: 2936

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
Q	5,158,986	10/27/1992	Cha, S.W., et al.	521	82	04/05/91
Q	5,334,356	08/02/1994	Baldwin, D.F., et al.	422	133	08/24/92

FOREIGN PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No
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OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

Q	"Packaging", <u>Electronic Materials Handbook, Volume 1</u> , ASM International, pp. 105, 768-769, (1989)
	"Properties and Selection: Nonferrous Alloys and Pure Metals", <u>Metals Handbook Ninth Edition, Vol. 2</u> , ASM International, pp. 157, 395, (1979)
	Chiniwalla, N., et al., "Structure-Property Relations for Polynorbornenes", <u>Proceedings from the Eighth Meeting of the Dupont Symposium on Polyimides in Microelectronics</u> , pp. 615-642, (1998)
	Jayaraj, K., et al., "Low Dielectric Constant Microcellular Foams", <u>Proceedings from the Seventh Meeting of the DuPont Symposium on Polyimides in Microelectronics</u> , pp. 474-501, (September 1996)
	Jin, C., et al., "Porous Xerogel Films as Ultra-low Permittivity Dielectrics for ULSI Interconnect Applications", <u>Conference Proceedings ULSI XII - 1997 Materials Research Society</u> , pp. 463-469, (1997)
	Miller, R.D., et al., "Low Dielectric Constant Polyimides and Polyimide Nanofoams", <u>Seventh Meeting of the DuPont Symposium on Polyimides in Microelectronics</u> , pp. 443-473, (September 1996)
	Ramos, T., et al., "Nanoporous Silica for Dielectric Constant Less Than 2", <u>Conference Proceedings ULSI XII - 1997 Materials Research Society</u> , 455-461, (1997)
	Shibasaki, T., et al., "Process and Application of Fumed Silica AEROSIL", <u>3rd Annual Workshop on Mechanical Polishing</u> , Lake Placid, New York, pp. 1-27, (1998)
Q	Singer, P., "The new low-k candidate: It's a gas", <u>Semiconductor International</u> , 22(3), pg. 38, (1999)

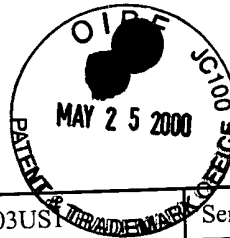
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Sheet 2 of 2

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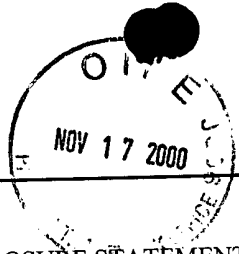
Q	Ting, C.H., "Low K Material/Process Development", <u>1996 VLSI Multilevel Interconnection State-of-the-Art Seminar</u> , pp. 171-212, (June 1996)
G	Van Vlack, L.H., <u>Elements of Materials Science</u> , Addison-Wesley Publishing Co., Inc. Reading, MA, pg. 468, (1959)
G	Vardaman, E.J., "Future Packaging Trends: CSP vs. Flip Chip", <u>11th European Microelectronics Conference</u> , pp. 295-299, (1997)

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						If Appropriate
<u>B</u>	5,821,621	10/13/1998	Jeng, S.	257	759	10/10/96
<u>Q</u>	5,879,787	03/09/1999	Petefish, W.G.	428	209	11/08/96
<u>A</u>	6,077,792	06/20/2000	Farrar, P.A.	438	780	07/14/97

FOREIGN PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
<u>Q</u>	2158995A	11/20/1985	Great Britain	H01Q	17/00		
<u>F</u>	578856A1	01/19/1994	European	H01L	21/334		

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

**Examiner Initial	
<u>GA</u>	Volksen, W., et al., "Characterization and Processing Considerations for Methylsilsesquioxane Based Dielectrics", <u>Proceedings of the Fifth Dielectric for ULSI Multilevel Interconnections</u> , Santa Clara, CA, pp. 83-90, (1999)

Examiner

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